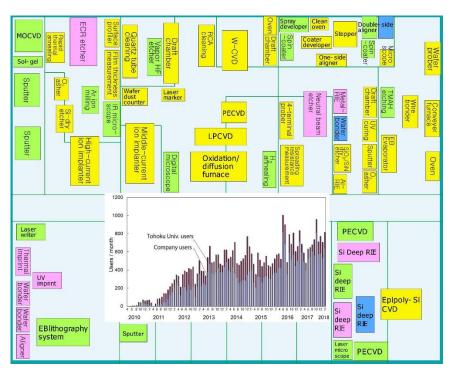
Hands-on access fab. (K.Totsu et.al.)

Shared facility for industry to prototype MEMS devices (4 / 6 inch). Companies which cannot prepare their own facility dispatch their employees to operate equipments by themselves. The facility is located in 1800m² clean room, which was used for the production of power transistor and newly installed MEMS fabrication equipments.

http://www.mu-sic.tohoku.ac.jp/coin/index.html

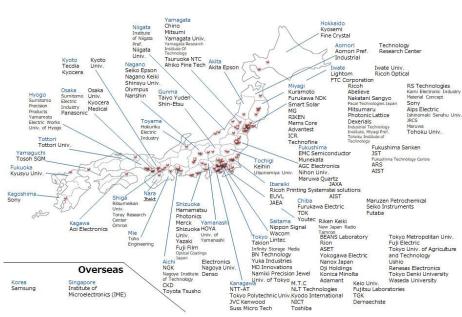
Contact person: Associate professor Kentaro Totsu Phone 022-229-4113, totsu@mems.mech.tohoku.ac.jp







Layout and number of users







More than 200 users (companies and institute)

Hands-on-access Fab. Equipment List

PE-CVD ~8"

Sumitomo MPX-CVD

國

Sputtering

~8"

MOCVD

~8"

Wacom Doctor-T PZT, up to 8inch

Chemical dry etcher

(CDE)

Shibaura CDE-7

AI RIE

Shibaura HIRRIF 100

КОН-ТМАН

Surface profiler

~6"

IR microscope

~6"

Olympus, Hamamatsu

FE-SEM

Chip

Hitachi S5000

Line-focus-beam

microscope

Ultrasonic

microscope

~12

X-ray micro CT

· III D



FIR

~3"

SII SMI9200

TOF-SIMS

CAMECATOF-SIMS IV

~50mm

Origin electric Reprina-T50A MAX 650°C, 30kN

AFM

~8"

Digital Instrument